# Structural Characterization of the Silicon Trioxide Radical Cation (SiO<sub>3</sub><sup>•+</sup>) by Fourier-Transform Ion Cyclotron Resonance Mass Spectrometry and ab Initio MO Calculations

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Received October 25, 1993. Revised Manuscript Received March 30, 1994®

Abstract: Gas-phase experiments are performed aimed at a structural characterization of  $SiO_3^{+}$ , which is—as reported earlier [(a) Creasy, W. R.; O'Keefe, A.; McDonald, J. R. J. Phys. Chem. 1987, 91, 2848. (b) Wlodek, S.; Bohme, D. K. J. Chem. Soc., Faraday Trans. 2 1989, 85, 1643.]-readily available by oxidizing SiO2\*+ with N2O, and the combined experimental/theoretical results point to the formation of the covalently bonded trioxide 1. The absence of oxygen exchange in the thermoneutral reaction of SiO<sub>3</sub><sup>++</sup> with <sup>18</sup>O<sub>2</sub> as well as collision-induced dissociation (CID) experiments of SiO<sub>3</sub><sup>++</sup> rule out definitively a loosely bound ion-dipole complex [O<sub>2</sub>-SiO<sub>2</sub>]<sup>++</sup> for the initially generated  $SiO_3^{+}$  radical cation. In the near-thermal ion-molecule reactions of  $SiO_3^{+}$  with X (X = H<sub>2</sub>O, N<sub>2</sub>O, CH<sub>3</sub>CN, and  $C_2H_4$ ), the SiO(X)<sup>++</sup> products are formed with collision rate, and the kinetic isotope effects are negligibly small (1.1-1.3) when D<sub>2</sub>O, CD<sub>3</sub>CN, and C<sub>2</sub>D<sub>4</sub> are employed. The product SiO(H<sub>2</sub><sup>18</sup>O)<sup>++</sup>, generated from SiO<sub>3</sub><sup>++</sup> and H<sub>2</sub><sup>18</sup>O, upon collisional activation gives rise to SiOH<sup>+</sup> and Si<sup>18</sup>OH<sup>+</sup> in a nearly 1:1 ratio, thus pointing to a symmetrical intermediate. From bracketing experiments the standard enthalpy of formation of  $SiO_3^{*+}$  is estimated as 186 <  $\Delta H^{\circ}_{1298}(SiO_3^{++}) < 212 \text{ kcal/mol. Preliminary ab initio MO calculations (MP4SDTQ/6-31G*//MP2(Full)6-31G*))}$ of several SiO<sub>3</sub><sup>++</sup> isomers provide the following information: The  ${}^{4}A_{1}'$  state of the  $D_{3h}$ -symmetrical structure 1 is found to correspond to the global minimum, and the slightly distorted  $C_{2p}$  structure 2 (<sup>2</sup>A<sub>1</sub>) is 11.2 kcal/mol less stable than 1. The weakly bound ion-dipole complexes 5 and 6, which may serve as intermediates in the collision-induced dissociation of 1, are only destabilized by 2.2 and 5.5 kcal/mol relative to 1. For the  $C_{2\nu}$ -symmetric structures 3 and 4, there is no computational evidence that these radical cations exist as minima on either the doublet or quartet potential energy surfaces of SiO<sub>3</sub>\*+.

#### Introduction

While silicon oxides are ubiquitous on planet Earth's surface, these molecules are much less present<sup>1</sup> in extraterrestrial environments, and the anomalous distribution of atomic silicon in the ionosphere<sup>2</sup> has triggered numerous experimental and theoretical studies aimed at providing evidence for the pathways by which the depletion of ground-state Si\*+(2P) occurs. Reactions 1 and 2 were proposed<sup>3</sup> to be responsible for the formation of protonated silicon monoxide (SiOH<sup>+</sup>),<sup>4</sup> which upon ion-electron recombination (eq 2) is suggested to give rise to silicon monoxide in interstellar gas clouds.

Higher silicon oxides (SiO<sub>x</sub>;  $x \ge 2$ ) are also of interest in the context of studying the intriguing electronic and structural properties of polyoxides. While there exist several reports on the

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SI<sup>++</sup> + H<sub>2</sub>O 
$$\rightarrow$$
 SIOH<sup>+</sup> + H<sup>+</sup> (1)  
SIOH<sup>+</sup> + e<sup>-</sup>  $\rightarrow$  SIO + H<sup>+</sup> (2)

trioxides of carbon,<sup>5</sup> nitrogen,<sup>6</sup> and phosphorus,<sup>7</sup> data on the successful preparation or on a thorough theoretical characterization of the analogous neutral silicon trioxide SiO<sub>3</sub> have not yet been reported in the literature. The radical cations of silicon oxides,  $SiO_x^{*+}$  (x = 1-4), are available by a stepwise oxidation of atomic silicon ion (eq 3), and the rates of ion formation were measured<sup>8</sup> by using the selected ion flow tube (SIFT) technique.<sup>9</sup>

 $SI^{+} \rightarrow SIO^{+} \rightarrow SIO^{+}_{2} \rightarrow SIO^{+}_{3} \rightarrow SIO^{+}_{4}$ (3)

Due to the limitation of the SIFT method, a structural characterization of the higher silicon oxides  $SiO_x^{*+}$  (x = 3, 4) could not be achieved.<sup>10</sup> In this article we will report the results of near-thermal ion-molecule as well as collision-induced dissociation (CID) reactions of SiO<sub>3</sub><sup>•+</sup> using the technique of Fourier-

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transform ion cyclotron resonance (FTICR).<sup>11,12</sup> The experimental findings are complemented by preliminary ab initio MO studies of chemically feasible SiO<sub>3</sub><sup>•+</sup> isomers, including doublet and quartet states.13

### **Experimental and Computational Details**

The apparatus (a Spectrospin CMS-47X equipped with an external ion source14) and its operation have been described in detail previously.15 Atomic Si<sup>++</sup> is formed via laser desorption/ionization<sup>16</sup> by focusing the beam of a Nd:YAG laser (Spectron Systems, fundamental frequency 1064 nm) onto a silicon wafer which is affixed in the external ion source. The ions are extracted from the source and transferred into the analyzer cell by a system of electrostatic potentials and lenses. After deceleration, the Si\*+ ions are trapped in the field of the superconducting magnet (Oxford Instruments), which has a maximum field strength of 7.05 T. In order to quench the excited Si\*+(4P) state, which is cogenerated (<5%) under the present conditions, argon was admitted to the ICR cell with a constant pressure of ca.  $2 \times 10^{-7}$  mbar. Argon was also used as a collision gas in the CID experiments.<sup>17</sup> Any excited Si<sup>++</sup> states which may have survived the quenching procedure were removed by introducing  $H_2$  or  $D_2$  via a selenoid-pulsed valve;<sup>18</sup> from previous studies<sup>4b</sup> it is known that excited Si\*+ cations (4P and higher states) undergo facile reactions with molecular hydrogen, while ground-state  $Si^{+}(^{2}P)$  is nonreactive. Isolation of the most abundant isotope of silicon, i.e. 28Si\*+, was achieved by using FERETS,<sup>19</sup> and great care has been taken to avoid any offresonance excitation of the ions of interest.<sup>20</sup> The radical cation SiO<sub>3</sub><sup>•+</sup> was generated as described earlier<sup>8,10b</sup> by reacting Si<sup>++</sup> with a mixture of  $N_2O/Ar$  (1:10) which was pulsed-in using a second valve. The pressure in the reservoir was ca. 1 mbar, and the valve was opened for 30 ms. After 2 s the reagent gas was pumped away and the  $SiO_3^{\bullet+}$  ions were collisionally cooled and isolated as described above. The reagent gases used to probe the ion-molecule reactions of SiO<sub>3</sub><sup>•+</sup> were introduced via a second leak valve; depending on the ion gauge sensitivity, the pressure of the various gases, as measured with an ionization gauge (Balzers IMG 070), was ca.  $(5-10) \times 10^{-9}$  mbar. High-resolution and double-resonance experiments were performed as described earlier.<sup>15,21</sup> For the determination of the rate constants, ion gauge sensitivities, relative to N2, were taken from the literature<sup>22</sup> as were the polarizabilities<sup>23</sup> and dipole moments.<sup>23</sup> The experimentally determined rate constants,  $k_{\rm R}$ , which were obtained from the plot of log[SiO<sub>3</sub><sup>+</sup>] versus time, were compared with collision rate constants  $(k_{coll})$  as calculated by Su and Chesnavich.<sup>24</sup> A typical example is given in Figure 1 for the reaction of  $SiO_3^{+}$  with  $H_2O$ . The rate constants have error bars not exceeding  $\pm 25\%$ , and the errors are mostly due to different ion gauge sensitivities for different substances used for the calibration.25 All ICR experiments were conducted at room temperature (298 K). The thermochemical data used are summarized in Table 1.

The ab initio MO calculations of the SiO3\*+ isomers pertinent to this study were performed on an IBM/RISC 6000 workstation using the

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Figure 1. Time evolution of the  $SiO_3^{\bullet+}$  (+) and  $SiO(H_2O)^{\bullet+}$  (×) ion intensities in the reaction  $SiO_3^{*+} + H_2O \rightarrow SiO(H_2O)^{*+} + O_2$ . While the neutral molecules are at room temperature ( $p_{\rm H_2O} \approx 1.5 \times 10^{-8} \, {\rm mbar}$ ), the ions are not.

**Table 1.** Standard Enthalpy of Formation ( $\Delta H^{o}_{f,298}$ ) for Ions and Neutrals As Discussed in the Text<sup>a</sup>

ion	$\Delta H^{\circ}_{f,298}$ (kcal/mol) neutra		$\Delta H^{\circ}_{f,298}$ (kcal/mol)	
Si**	295	N <sub>2</sub> O	20	
SiO++	240	H <sub>2</sub> O	-58	
SiO <sub>2</sub> •+	1926	SiO <sub>2</sub>	-73 <sup>6</sup>	
SiO <sub>3</sub> •+	199°	C₂H₄	13	
O <sub>2</sub> •+	279	CH <sub>3</sub> CN	18	

<sup>a</sup> Unless stated otherwise, all values are taken from ref 26. Uncertainties are  $\pm 2 \text{ kcal/mol}$  except for SiO<sub>2</sub><sup>\*+</sup> and SiO<sub>3</sub><sup>\*+</sup> (see text and ref 30). <sup>b</sup> Taken from ref 8b. <sup>c</sup> This work. Also, see comments in ref 30.

GAUSSIAN 92 program package.27 For the geometry optimization the standard polarized split valence basis set 6-31G\* 28 has been used in the framework of the Møller-Plesset (MP) perturbation theory,<sup>29</sup> terminated at the second order. For the evaluation of relative stabilities, fourthorder perturbation theory has been applied including single, double, triple, and quadruple excitations (MP4SDTO). While in the MP2-calculated geometries all electrons have been included in the correlation (MP2-(Full)), in the MP4SDTO calculations only the valence electrons were correlated. In addition to the single-determinant-based perturbational treatment, we performed single-point MCSCF calculations (correlating seven electrons in nine orbitals) using the MP2(Full)-optimized geometries. This procedure was necessary because the expectation values  $\langle S^2 \rangle$  for the spin projection operator indicated quite large spin contaminations of the wave functions for some of the doublet-state isomers of SiO3<sup>•+</sup>.

#### **Results and Discussion**

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As reported earlier,<sup>8</sup> the SiO<sub>3</sub><sup>•+</sup> species is accessible by consecutive oxidation commencing with atomic silicon ions. Attempts to oxidize SiO<sub>3</sub><sup>•+</sup> with N<sub>2</sub>O to SiO<sub>4</sub><sup>•+</sup> (m/z 92) failed under ICR conditions. At the detection limit of the ICR machine, no SiO<sub>4</sub><sup>•+</sup> is formed; rather, the ionic products, shown in eq 4, are obtained. The occurrence of reaction 4a, together with the formation of  $SiO_3^{+}$  (eq 5), permits an estimate of the standard enthalpy of formation of  $SiO_3^{+}$  by using the thermochemical data given in Table 1, and we arrive at  $186 < \Delta H^{\circ}_{f,298}(SiO_3^{*+})$ < 212 kcal/mol.<sup>30,31</sup>

$$SIO_3^{+} + N_2O \xrightarrow{0.9} O_2^{+} + SIO_2 + N_2$$
 (4a)

$$D_2^{+} + N_2 O \longrightarrow SiO_3^{+} + N_2$$
 (5)

Next, we will describe several experiments aimed at obtaining insight in the connectivities of the SiO3\*+ radical ion, for which several structures are chemically feasible.

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Figure 2. CID experiments of SiO<sub>3</sub><sup>•+</sup> (collision gas, argon).

If SiO<sub>3</sub><sup>\*+</sup> is subjected to CID experiments with argon as a collision partner, over the whole kinetic energy range applied (Figure 2) the only products formed correspond to SiO<sup>\*+</sup> and O<sub>2</sub><sup>\*+</sup> favoring reaction 6a for all kinetic energies. This is not surprising, as—on the basis of thermochemical data—path 6a is 15 kcal/mol less energy demanding than reaction 6b.

$$SIO_3^{++}$$
  $CID$   $\rightarrow$   $SIO^{++} O_2$  (6a)  
 $O_2^{++} + SIO$  (6b)

In the collision experiments no products are observed for the deoxygenation of  $SiO_3^{*+}$  (eq 7). While this process is energetically 3 kcal/mol less demanding than process 6b, the large uncertainty  $(\pm 20 \text{ kcal/mol})^{8b}$  in the standard enthalpy of formation of  $SiO_2^{*+}$  makes this supposition less convincing, and reaction 7 may well be the most energetically demanding of the three channels.

$$SIO_3^{++} \xrightarrow{CID} SIO_2^{++} + 0$$
 (7)

The CID results suggest that, in the course of the collision events, the  $SiO_3^{*+}$  species prior to dissociation quite likely isomerizes to an ion-dipole intermediate which contains the two building blocks SiO and O<sub>2</sub>. This intermediate, in turn, serves as the immediate precursor for the formation of the products shown in eq 6a, b and in Figure 2, i.e.  $SiO^{*+}/O_2$  and  $O_2^{*+}/SiO$ . In addition to the thermochemical arguments (see above), formation of  $SiO_2^{*+}/O$  is not expected to take place from an ion-dipole complex  $[O_2-SiO]^{*+}$ .

While a loosely bound ion-dipole complex is most likely involved as an intermediate in the CID experiment, such a structure cannot be assigned to the SiO<sub>3</sub><sup>•+</sup> species *initially generated* in the sequential oxidation of the atomic silicon cation (eqs 3 and 5). This conclusion is based on the observation that the thermoneutral exchange process with dioxygen (eq 8) does not take place. If the SiO<sub>3</sub><sup>•+</sup> product of eq 5 would correspond to a loosely interacting ion-dipole complex  $[O_2-SiO]^{\bullet+}$ , replacement of  $O_2$  by its isotopomer <sup>18</sup>O<sub>2</sub> is expected to occur, as these kind of complexes are known to undergo facile exchange reactions.<sup>32</sup>

$$SIO_3^{+} + {}^{18}O_2 - - - SIO_{3x}{}^{18}O_x^{+} + O_x{}^{18}O_{2x}$$
 (8)

However, replacement of molecular oxygen is the dominant reaction channel in the ion-molecule reactions of  $SiO_3^{*+}$  with various neutral molecules M (eq 9).

While the  $O_2$  expulsion is not observed for  $M = O_2$ ,  $N_2$ ,  $H_2$ ,  $CO, CO_2$ , and  $CH_4$ , respectively, thus indicating that the reactions

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Table 2. Rate Constants (in Units of  $10^{-10}$  cm<sup>3</sup> molecule<sup>-1</sup> s<sup>-1</sup>) for the Reactions of SiO<sub>3</sub><sup>++</sup> with Neutral Molecules M at 298 K

М	products	k <sub>R</sub>	k <sub>coll</sub>	reaction efficiency <sup>c</sup>
N <sub>2</sub> O	$[SiN_2O_2]^{*+} + O_2^{a,b}$	8	8.1	0.99
H <sub>2</sub> O	$\dot{S}iO(\dot{H}_2\dot{O})^{*+} + \dot{O}_2$	23	23.8	0.97
CH <sub>3</sub> CN	$SiO(CH_3CN)^{++} + O_2^{b}$	34	36.0	0.94
C₂H₄	$SiO(C_2H_4)^{*+} + O_2^{b}$	11	10.7	1.03
		10		

<sup>a</sup> For the other products, see eq 4a. <sup>b</sup> See ref 30. <sup>c</sup> Defined as  $k_R/k_{coll}$ .

$$\mathrm{SIO}_{3}^{*+} + \mathrm{M} \longrightarrow [\mathrm{O}_{2} - \mathrm{SI}(\mathrm{O})\mathrm{M}]^{*+} \longrightarrow \mathrm{SI}(\mathrm{O})\mathrm{M}^{*+} + \mathrm{O}_{2} \qquad (9)$$

do not take place at all or with rate constants  $k_{\rm R} < 10^{-13}$  cm<sup>3</sup> molecule<sup>-1</sup> s<sup>-1</sup>, the processes are extremely efficient with M = C<sub>2</sub>H<sub>4</sub> and the polar molecules M = N<sub>2</sub>O, H<sub>2</sub>O, and CH<sub>3</sub>CN (Table 2). The efficiency of O<sub>2</sub> expulsion is demonstrated by a comparison of the experimentally determined rate constants,  $k_{\rm R}$ , with the calculated<sup>24</sup> collision rate constants,  $k_{\rm coll}$ . As shown in the last column of Table 2, evaporation of O<sub>2</sub> occurs for all molecules near or with collision rate, and when the ion-molecule reactions of SiO<sub>3</sub><sup>•+</sup> are performed with D<sub>2</sub>O, C<sub>2</sub>D<sub>4</sub>, and CD<sub>3</sub>CN, the kinetic isotope effects (KIEs) on the rate constants are negligibly small (KIE  $\approx 1.1$ –1.3).

For the mechanism of  $O_2$  substitution by M (eq 9) several scenarios are conceivable. As often invoked in gas-phase ionmolecule reactions, the process may proceed via an ion-dipole intermediate  $[O_2-Si(O)M]^{*+}$ , as indicated in eq 9. However, as suggested by a reviewer, the reaction of SiO<sub>3</sub><sup>\*+</sup> with M could also be viewed as bond rearrangement processes, triggered by an initial electrostatic interaction of the positive charge on SiO<sub>3</sub><sup>\*+</sup> (mostly located on the silicon atom as shown further below) with M. Indeed, the results obtained for the reaction of SiO<sub>3</sub><sup>\*+</sup> with H<sub>2</sub><sup>18</sup>O point to the operation of bond rearrangements.

While most of the ionic products  $Si(O)M^{*+}$  formed in process 9 were not structurally characterized, some insight was obtained for the reaction with  $M = H_2^{18}O$ . Collision-induced decomposition of the resulting  $SiO(H_2^{18}O)^{*+}$  product gives rise to a 1:1 formation of  $SiOH^{*+}/Si^{18}OH^{*+}$  (eq 10) throughout the kinetic energy regime applied. This indicates that symmetric silicon dihydroxide ion  $SiOH(^{18}OH)^{*+}$  acts as an intermediate in the course of the reaction. However, this experiment does not permit an unequivocal determination of the stage of the overall reaction at which the isomerization  $SiO(H_2^{18}O)^{*+} \rightarrow SiOH(^{18}OH)^{*+}$  takes place.<sup>33</sup>

$$SIO_{5}^{+} + H_{2}^{18}O \xrightarrow{\cdot O_{2}} SIO(H_{2}^{18}O)^{+} \xrightarrow{\bullet} SIOH^{(18}OH)^{+} \xrightarrow{CID} \xrightarrow{\bullet} SIOH^{+}$$
(10)

Although the experimental findings are in keeping with the formation of a *covalently* bonded  $SiO_3^{*+}$  species in the oxidation of  $SiO_2^{*+}$  with  $N_2O_3^{34}$  unambiguous structural assignment, i.e. a distinction between 1, 2, and 3 (Chart 1), is not possible on the basis of these experiments alone. While ion-dipole complexes of the general structure  $[O_2-SiO]^{*+}$  are involved as intermediates in the collision-induced decomposition of  $SiO_3^{*+}$  (eq 6) and perhaps also in the ion-molecule reactions of  $SiO_3^{*+}$  with neutral molecules M (eq 9), these species neither are formed as the initial oxidation product (eq 5) nor correspond to the global minimum on the potential energy surface (PES) of  $SiO_3^{*+}$ . The latter aspect is supported by ab initio MO calculations which will be referred to briefly.<sup>13</sup> At all theoretical levels used, the global minimum

<sup>(30)</sup> We agree with the comment of a reviewer that, in view of the very large uncertainty in  $\Delta H^{\circ}_{1296}(\text{SiO}_2^{*+})$  of  $\pm 20 \text{ kcal/mol}^{\circ}$  and the problems inherently associated with deriving thermochemical data from bracketing experiments, the estimate of  $\Delta H^{\circ}_{1298}(\text{SiO}_3^{*+})$  is only qualitative. In line with this, no corrections were made for entropy effects.

<sup>(31)</sup> While the elemental composition of the ionic product of reaction 4b as well as the products formed in the reactions of  $SiO_3^{++}$  with other neutral molecules M (eq 9) has been established by high-resolution FTICR, no attempts were made to structurally characterize the resulting radical cations.

<sup>(33)</sup> Ligand switching reactions strongly suggest that from the initially formed SiO(H<sub>2</sub><sup>18</sup>O)<sup>++</sup> ion both H<sub>2</sub>O and H<sub>2</sub><sup>18</sup>O are exchanged in a 1:1 ratio. This points to a facile reversible isomerization SiO(H<sub>2</sub><sup>18</sup>O)<sup>++</sup>  $\Rightarrow$  Si(OH)-(O<sup>18</sup>H)<sup>++</sup> prior to CID experiments. This view is also underlined by preliminary ab initio MO studies (Fiedler, A. Unpublished results).

<sup>(34)</sup> We do not object to a reviewer's comment that "formation of  $SiO_3^{*+}$ from  $SiO_2^{*+}$  by oxygen atom transfer from  $N_2O$  can be expected to result in structure 1. It is energetically favoured as well as mechanistically (electrostatic considerations suggest that the O-atom attack will be on the positively charged Si site in  $SiO_2^{*+}$ ".

Chart 1. MP2(Full)/6-31G\*-Calculated Geometries of Some SiO<sub>3</sub><sup>•+</sup> Isomers<sup>a</sup>



<sup>*a*</sup> Bond lengths are given in Å and bond angles in deg. 1 corresponds to the quartet state  ${}^{4}A_{1}'$ , 2 to a doublet state  $({}^{2}A_{1})$ ; 5 and 6  $({}^{4}A'')$  are ion-dipole complexes of SiO<sup>++</sup>  $({}^{2}\Sigma)$  and O<sub>2</sub>  $({}^{3}\Sigma_{g}^{-})$ .

corresponds to the  $D_{3h}$ -symmetrical structure 1. The MP2calculated bond length (Chart 1) of 1.648 Å is almost identical with the SiO bond length of 1.650 Å obtained at MP4SDTQ.<sup>35</sup> The three unpaired electrons of the <sup>4</sup>A<sub>1</sub>' state of 1 occupy the a<sub>1</sub>' ( $\epsilon_i = -0.905$  hartree) and 2e' ( $\epsilon_i = -0.866$  hartree) orbitals, which are localized on the three oxygen atoms. The positive charge, as calculated by a Mulliken population analysis, is located on the central silicon atom (1.69 e) while each of the three oxygen atoms is negatively charged (-0.23 e). The  $<S^2>$  value of 3.770 for 1 indicates only a small contamination of the single-determinant wave function, and this result is consistent with the data from a MCSCF calculation according to which this configuration contributes to the wave function with 97%.

In contrast, for the doublet electromer of 1, the wave function is heavily contaminated by higher spin contributions, as suggested by a value of  $\langle S^2 \rangle = 1.768$ . In addition, according to the MP2-(Full) geometry optimization, the doublet state of 1 is distorted from  $D_{3h}$ - to  $C_{2b}$ -symmetry, and the structural data of the electromer 2 (<sup>2</sup>A<sub>1</sub>) are given in Chart 1. The electronic structure of 2 (<sup>2</sup>A<sub>1</sub>) is quite similar to that of 1 (<sup>4</sup>A<sub>1</sub>'). The three unpaired electrons are localized at the oxygen atoms, and the Mulliken population analysis places the positive charge on the silicon center (1.67 e), while the oxygen atoms are negatively charged (-0.23 e for the "axial" oxygen and -0.22 e for each of the two "in plane" oxygen atoms). MCSCF calculations indicate that the wave function consists of two contributions (46% and 52% each) which differ only in the  $\alpha,\beta$  spins at the oxygen atoms. With regard to the relative stability, 2 is calculated (MP4SDTQ//MP2(Full)/ 6-31G\*) to be 11.2 kcal/mol less stable than 1.

All attempts to locate the  $C_{2\nu}$ -symmetrical structure 3 on either the quartet or doublet potential energy surface of SiO<sub>3</sub><sup>•+</sup> failed, in that the geometry optimization resulted in structures 1 or 2. Similarly, the T-shaped,  $C_{2\nu}$ -symmetric ion-dipole complex 4 could not be located as a stationary point of the SiO<sub>3</sub><sup>++</sup> potential energy surface. However, the complexes 5 and 6 were found to exist as genuine minima on the quartet surface. These two  $C_s$ symmetrical structures correspond to weakly bound complexes of SiO<sup>++</sup> ( $^{2}\Sigma^{-}$ ) and O<sub>2</sub> ( $^{3}\Sigma_{g}^{-}$ ) as indicated by the long distances of 2.165 (5) and 2.371 Å (6) separating the two building blocks. In addition, the perturbation of the  $O_2$  molecules in 5 and 6 by the SiO+ radical cation is rather small; this follows directly from a comparison of the O-O bond lengths in 5 and 6 (1.229 and 1.221 Å) as compared with the MP2(Full)-calculated O-O bond length of 1.225 Å for the free oxygen molecule. Interestingly, 5 and 6 are only slightly less stable than 1 (5.0 and 2.0 kcal/mol) and therefore may indeed serve as intermediates en route in the collision-induced dissociation of 1 (eq 6): The evaporation of  $O_2$ to generate SiO<sup>++</sup> is the energetically favored reaction channel (see Figure 2) over the whole energy regime. Formation of  $O_2^{*+}$ , which was accompanied by loss of SiO (reaction 6b), is also favorable, since it only requires electron transfer from O2 to SiO++ prior to separation of the ion-dipole complexes 5 and 6.

In conclusion, while more elaborate quantum mechanical calculations are necessary to map out the complete potential energy surface of SiO<sub>3</sub><sup>•+</sup>,<sup>13</sup> the combined experimental/theoretical results strongly suggest that SiO<sub>3</sub><sup>•+</sup> formed in the gas-phase oxidation of SiO<sub>2</sub><sup>•+</sup> with N<sub>2</sub>O (eq 5)<sup>8</sup> corresponds to the  $D_{3h}$ -symmetric species 1.

Acknowledgment. The generous support of our work by the Deutsche Forschungsgemeinschaft and the Fonds der Chemischen Industrie is appreciated. We are grateful to Prof. D. K. Bohme for helpful comments and Dipl.-Chem. A. Fiedler for preliminary MO calculations on the  $SiO(OH_2)^{++}$  system.

<sup>(35)</sup> This excellent agreement prompted us not to employ the very expensive MP4SDTQ calculations for the geometry optimization of the other  $SiO_3^{++}$  species shown in Chart 1.